

New Strategy for the Growth of Complex Heterostructures Based on Different 2D Materials

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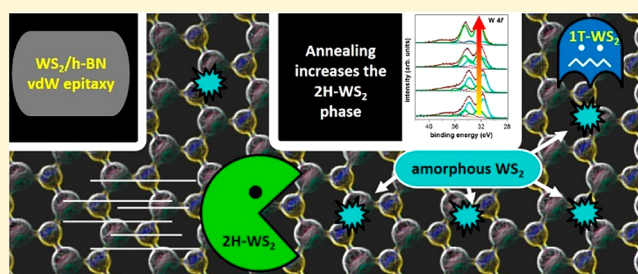
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ABSTRACT: Tungsten disulfide (WS_2) monolayers have been synthesized under ultra high vacuum (UHV) conditions on quasi-free-standing hexagonal boron nitride (h-BN) and gold deposited on Ni(111). We find that the synthesis temperature control can be used to tune the WS_2 structure. As documented by in situ core level and valence band photoemission and by ex situ Raman spectroscopy, the partially disordered WS_2 layer obtained at room temperature transforms to the 2H- WS_2 phase at about 400 °C. Low energy electron diffraction confirms the existence of van der Waals epitaxy between WS_2 and h-BN and gold substrates. The measured band structure indicates that the WS_2 electronic structure is not affected by the interaction with the h-BN and gold substrates.



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INTRODUCTION

Since the isolation of monolayer graphene by Geim and Novoselov in 2004,¹ two-dimensional materials have received major attention. In particular, interest in hexagonal boron nitride (h-BN) and transition metal dichalcogenides (TMDs) has surged in recent years due to their wide range of electronic properties ranging from insulating (h-BN) to semiconducting (TMDs). Moreover, monolayer systems of h-BN and TMDs offer interesting optical and electronic properties that differ from their bulk counterparts.^{2–5} Monolayer semiconducting TMDs are attractive candidates for future optoelectronics, including flexible electronics,^{2,6,7} and even spintronics.⁸ Additionally, MoS_2 and WS_2 are already widely used in catalytic applications including hydrotreating, hydrocracking,⁹ and hydrogen evolution reaction (HER).^{10,11} However, h-BN exhibits a bandgap of 5.97 eV,¹² making it an attractive candidate for solar blind detectors, UV lasers, low-k dielectric materials for 2D devices,^{13–16} and when coupled with magnetic metal substrates can exhibit ferrimagnetism.¹⁷

Currently, the focus is on heterogeneous systems, called van der Waals heterostructures, where monolayers of different 2D materials are stacked vertically layer-by-layer, or stitched together seamlessly in-plane to form lateral heterojunctions. Many physical properties have been explored in such van der Waals heterostructures, and devices with improved performances have been demonstrated.^{5,18–22} For example, monolayer TMD heterostructures artificially stacked by mechanical transfer techniques,⁵ i.e., WS_2/MoS_2 ^{23,24} and $\text{WSe}_2/\text{MoS}_2$,²⁵

exhibit interlayer coupling that enables electron–hole recombination between layers that modifies their optoelectronic properties. By placing h-BN layers in between TMD layers, the coupling can be modulated.²⁵ However, fabrication of 2D heterostructures with clean and sharp interfaces, essential for preserving their intrinsic properties, remains a challenge.

Mechanical transfer methods have major drawbacks: the stacking orientation cannot be precisely controlled, the interface between layers can be easily contaminated,²⁶ and the presence of metal or polymer residues in contact with the 2D layers modifies their pristine properties^{27,28} and the characteristics of the desired heterojunctions.⁶ However, there are still only a few reports of directly grown 2D heterostructures with TMDs,^{29–31} indicating that a concerted effort is needed in developing direct growth methods of these structures.³² Single layer WS_2 has been obtained by chemical vapor deposition (CVD) on transferred h-BN,³³ whereas WS_2/MoS_2 in-plane and stacked heterojunctions have been grown by CVD.³⁴ The production method of 2D heterostructures is a crucial factor for their future scale-up and implementation into industrial applications. As a result, CVD and molecular beam epitaxy (MBE)³⁵ techniques may be considered industrial standards for building advanced device structures.

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MoS₂ has been widely investigated,³⁶ however other TMDs such as WS₂ have received less attention. Two of the most characteristic phases of WS₂ are the 1T (octahedral) and 2H (trigonal prismatic) phases.³⁷ The former is metallic and metastable, whereas the latter is semiconducting and thermodynamically favored. Because of its instability, the 1T phase can be irreversibly converted into the 2H polymorph by annealing at 300–400 °C.¹⁰ The 1T phase can be formed from bulk 2H crystals by intercalating alkali metals,¹⁰ or by irradiation with high-energy electrons, as in transmission electron microscopy (TEM).³⁷ The 1T-WS₂ metallic phase is important because its conductive behavior boosts the activity for HER, achieving performance comparable to commercial platinum catalysts.¹⁰ Thus, recent research has focused on direct deposition and stabilization of the metastable metallic phase. Because of the disadvantages of the alkali metal intercalation (partial damage of the layer by strain³⁰ and reactions to form Li₂S³⁸), some recently proposed methods include colloidal synthesis³⁹ and stabilization via donor doping.⁴⁰

In this paper, we report the synthesis of single layer WS₂ on quasi-free-standing h-BN (i.e., h-BN/Au/Ni(111)) and on a traditional “3D” substrate Au/Ni(111) and demonstrate the realization of new artificially stacked solids. The syntheses were carried out in ultra high vacuum (UHV) in order to study the pristine properties and to create stacked heterojunctions without air contamination/oxidation or the presence of residue as result of transfer procedures.²⁶ We find that the structure of the WS₂ is “tunable”, as it depends strongly on the synthesis temperature. For WS₂ films grown at low temperatures, we find that the XPS data are consistent with the presence of 1T-WS₂, which subsequently transforms into 2H-WS₂ at temperatures comparable to those reported for 1T → 2H phase transition;¹⁰ however, Raman spectroscopy, low energy electron diffraction (LEED) and valence band (VB) ultraviolet photoemission spectroscopy (UPS) data indicate the presence of a disordered structure formed by both amorphous and 2H-WS₂ phases at low temperatures. Our data suggest that the XPS signal attributed to the 1T phase in previous reports,^{10,39,41} may be partly due to the presence of amorphous WS₂.

Our data are comparable to a previous scanning tunneling microscopy (STM) study where the growth of few-nanometer wide single layer WS₂ islands on Au(111) was observed:⁴² the deposition of WS₂ at low temperature leads to a disordered structure, while thermal treatment triggers the formation of ordered 2H-WS₂. Another work⁴³ presented a valence band study of bulk and single layer 2H-WS₂ supported on highly oriented pyrolytic graphite (HOPG). This demonstrates that highly controlled single layer films of WS₂ can be grown under UHV conditions on several substrates by carefully controlling the growth procedure; however, a complete photoemission study, from core level to valence band, of the evolution from disordered to ordered WS₂ on a “3D” and “2D” substrates is missing in the literature.

■ EXPERIMENTAL SECTION

Samples were prepared and examined in situ in UHV (<10⁻⁹ mbar) by XPS, to determine the surface composition, UPS, to study the VB structure, LEED, to determine the degree of the long-range order, and ex situ by Raman spectroscopy, to confirm the presence of 2H-WS₂. Typically, the tungsten 4f (W 4f) photoemission line is exploited to understand which polymorph of WS₂ has been obtained, and its evolution with the annealing temperature is used to characterize the

structural changes.^{10,39,41} Additionally, TEM,¹⁰ X-ray diffraction (XRD),³⁹ or Raman spectroscopy are used to confirm the octahedral environment for W, but these techniques cannot exclude a priori the presence of a disordered part in the layer.

Materials Preparation. To synthesize the 2D heterostructures, a Ni(111) single crystal substrate was chosen because it allows facile growth of high quality h-BN layers in UHV; the resulting layer can also be electronically decoupled by intercalating gold underneath.⁴⁴ The Ni(111) single crystal was cleaned by repeated cycles of sputtering (1.5 kV, 1 × 10⁻⁶ mbar of Ar) and annealing at 800 °C; the surface cleanliness was verified by photoemission and LEED. h-BN monolayers were synthesized by dosing 2 × 10⁻⁷ mbar a borane–ammonia complex (NH₃–BH₃) on the Ni(111) at 700 °C. The precursor was placed in a flanged glass tube, heated at 80 °C, and dosed via a leak valve. In order to intercalate gold underneath h-BN, few layers of Au (about 6 ML) were deposited on h-BN/Ni(111) surface, while annealing the crystal at 400 °C, using electron-beam evaporation.

Tungsten disulfide layers were obtained by evaporating W in an atmosphere of 2 × 10⁻⁸ mbar of sulfur vapor, while annealing the sample at 120 °C and post treating at 400 °C to achieve the semiconducting trigonal prismatic phase (2H).⁴⁰ It is also possible to obtain directly 2H-WS₂ by depositing W in the presence of S vapor while annealing the crystal at 400 °C. Sulfur vapors were obtained by placing elemental sulfur in a glass vial connected to the main preparation chamber via a gate valve. The introduced sulfur is likely of the form S₆ or S₈ clusters.⁴⁵ The use of sulfur, instead of H₂S⁴² has been chosen for safety of the operator, H₂S is a highly toxic and flammable gas, and because of the low pressure necessary to fully sulfurize W layers deposited at rate of about 0.1 ML/min. This is probably due to the higher oxidation number of the sulfur chains with respect to the already reduced H₂S; the sulfurization reaction of metallic W is facilitated by this redox reaction.

Both tungsten and gold evaporation rates were calibrated using angle resolved XPS measurements according to the method reported in ref 46. A crosscheck of the amount of deposited material has also been carried out by XPS after film preparation.

Characterization. All XPS lines were acquired with a conventional Al K_α source with pass energy (PE) of 20 eV; the BE scale was calibrated by normalizing the Au 4f_{7/2} binding energy (BE) position to 84.0 eV. Photoemission lines were separated into single chemically shifted components (after Shirley background subtraction) using symmetrical Voigt functions with a full width at half-maximum (fwhm) of 1.35 eV. VB spectra were acquired with a standard Helium discharge source with PE = 2 eV for He I and PE = 10 eV for He II, spectra were acquired in the Γ direction of the Brillouin zone (i.e., normal emission) with an analyzer angular acceptance of 3°. Angle resolved photoemission spectroscopy (ARPES) measurements were accomplished at the ELETTRA beamline APE with photons of 40 eV, PE = 10 eV and energy resolution of 20 meV, the electron analyzer angular resolution was better than 0.2°. Raman spectra were acquired with a ThermoFisher DXR Raman microscope using a 532 nm laser (1 mW), focused on the sample with a 50× objective (Olympus) obtaining a spot size of about 1 μm.

■ RESULTS AND DISCUSSION

We have investigated, in a systematic way, the different types of interfaces that arise from growing WS₂ on “2D” and “3D” substrates, with the aim of understanding the effects originating from variations in electronic coupling. Following a strict reductionist approach, we have studied in detail the following heterostructures h-BN/Ni(111), h-BN/Au/Ni(111), WS₂/Au/Ni(111), and finally WS₂/h-BN/Au/Ni(111). In this context, h-BN and gold represent the prototypical atomic thin insulating layer and “3D” metal contact, respectively. In the following pages, the results of each different interface will be reported separately.

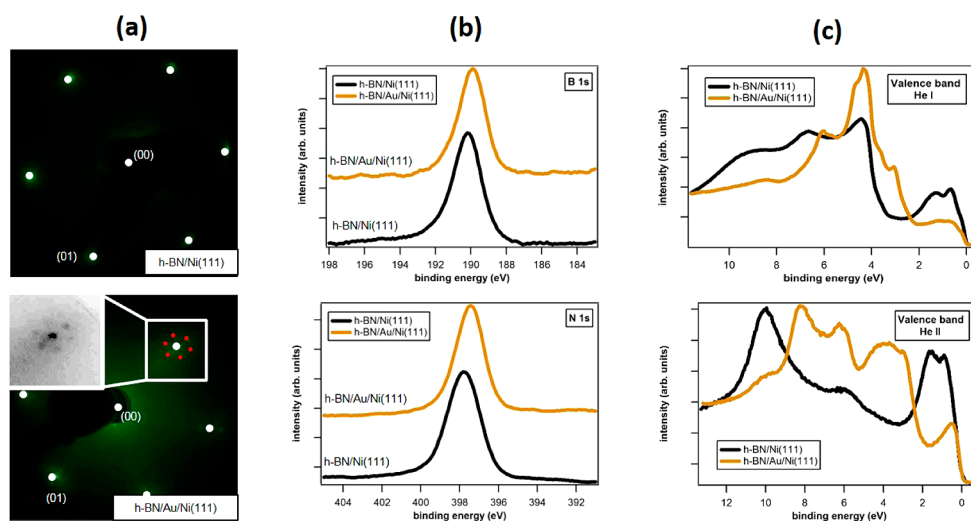


Figure 1. (a) LEED images, acquired at 70 eV, of h-BN/Ni(111) (1×1) reconstruction, h-BN/Au/Ni(111) a (9×9), the inset shows a magnified view of 6-fold h-BN diffraction spots around one of the substrate integer diffraction beams. (b) Photoemission from B 1s and N 1s core levels and (c) VB photoemission spectra acquired with He I and He II source of h-BN/Ni(111) and h-BN/Au/Ni(111).

Growth of h-BN/Ni(111) and h-BN/Au/Ni(111). As explained in the Experimental Section, h-BN layers on clean Ni(111) were obtained by dehydrogenation of the borane-ammonia complex. Recently, it has been demonstrated that this molecule can be fully dehydrogenated to h-BN at high temperature.⁴⁷ Our data are comparable to the literature,^{44,48} where the borazine precursor was used.

The h-BN deposition is self-limiting to 1 ML and is characterized by a (1×1) structure with respect to the Ni(111) surface (as visible in Figure 1a); a deposition time of 10 min was used to ensure complete coverage. The insulating h-BN is tightly chemically bound to Ni substrate,¹⁷ but can be decoupled by intercalating gold in order to reach a quasi-freestanding state.⁴⁴ In order to do so, few layers (about 6 ML) of Au were deposited on the h-BN/Ni(111) surface, while annealing the crystal at 400 °C. The LEED patterns of h-BN/Ni(111) and h-BN/Au/Ni(111) are reported in Figure 1a. In the sample intercalated by Au, multiple diffraction spots with 6-fold symmetry can be observed around the integer reflections indicating the formation of an ordered (9×9) moiré superstructure between the unstrained h-BN and the Au(111) surface. The effect of gold intercalation can also be seen in the N 1s and B 1s photoemission lines (Figure 1b), that are shifted to lower BEs, and also in VB spectra (Figure 1c), where the h-BN π band moves from 9.9 to 8.2 eV, whereas the σ band shifts from 5.8 eV to about 4 eV, in agreement with ref 44. These electronic changes are related to the elimination of the chemisorption bonds between h-BN and Ni atoms and to the strain associated with the (1×1) epitaxy on Ni(111), in favor of relaxed physisorption of h-BN on the Au layer.

Growth of WS₂/Au/Ni(111). Monolayer WS₂ was grown on Au/Ni(111) at 120 °C and then annealed at 200 °C, 300 °C, and 400 °C; the effects of the thermal treatment on the W 4f photoemission lines is reported in Figure 2. The elemental composition of the deposited layer was determined by considering the integrated intensity of S 2p and W 4f photoemission peaks and using as an internal reference, an ex situ bulk sample of stoichiometric WS₂. It was found that the WS₂/Au/Ni(111) system composition, when deposited at 120 °C, was WS_{2.9}. The annealing process decreased the S/W ratio to WS_{2.5}. The WS_{2+x} stoichiometry can be explained by the

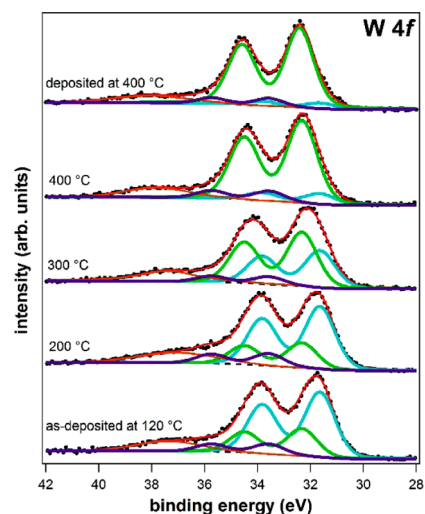


Figure 2. W 4f photoemission spectra of WS₂/Au/Ni(111): as-deposited at 120 °C and subsequently annealed at 200, 300, and 400 °C, or directly deposited at 400 °C. Measured data, Shirley background and total fit are represented with black dots, dashed black line and solid red line, respectively. Photoemission lines for amorphous WS₂, 2H-WS₂, WS₃, and W 5p_{3/2} are shown with blue, green, purple, and brown solid lines, respectively.

presence of nanometer domains, whose edges are S terminated, and by S adsorption on the substrate surface.⁴² As the sample is annealed, the area of the WS₂ islands increases, while reducing the area of edges.^{11,42} Moreover, the annealing process desorbs adventitious S that was deposited due to residual sulfur background.

No LEED pattern was discernible when depositing WS₂ at 120 °C while, after post treatment at 400 °C faint hexagonal diffraction spots were visible. To obtain a better diffraction pattern, WS₂ can be deposited directly on Au/Ni(111) at 400 °C. In this way, the W atoms have higher mobility and therefore can attain a more ordered and energetically stable structure. The corresponding LEED pattern is reported in Figure 3a, and shows six elongated spots forming a hexagonal cell corresponding to an incommensurate 2H-WS₂ film,

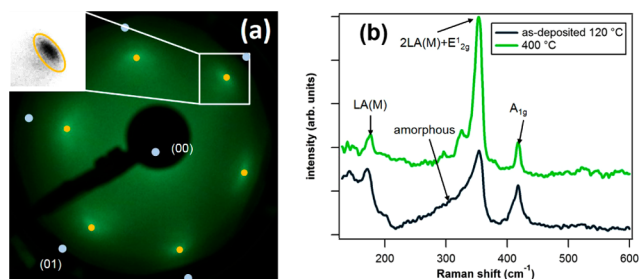


Figure 3. (a) LEED image acquired at 60 eV of WS₂/Au/Ni(111) deposited at 400 °C, inset showing a magnified view of a typical WS₂ diffraction spot; the white circles indicate calculated positions of Ni(111) diffraction spots. (b) Raman spectra of WS₂/Au/Ni(111) acquired with an excitation wavelength of 532 nm, before and after annealing at 400 °C.

whereas the substrate diffraction spots are heavily attenuated indicating that a fully covering monolayer film has formed.⁴³ The diffraction spots are about 10° wide, (see the inset in Figure 3a) indicating the presence of several rotational domains characterized by a small angle misalignment between the lattices of substrate and overlayer, similar to what was reported for the WS₂/HOPG system.⁴³ For low WS₂ coverage, several S/Au(111) reconstructions are detectable, as well.^{49,50}

The presence of 2H-WS₂, after annealing at 400 °C, was confirmed by ex situ Raman spectra reported in Figure 3b. Three principal peaks are visible: the first one at 176 cm⁻¹ corresponds to the longitudinal acoustic mode (LA(M)), the second one at 354 cm⁻¹ originates from the overlap of the second order mode 2LA(M) and the E_{2g}(Γ), whereas the third one at 417 cm⁻¹ corresponds to the first order A_{1g}(Γ). Moreover, the intensity ratio of the peaks at 354 and 417 cm⁻¹ confirms the presence of predominantly single layer 2H-WS₂.³ For the low temperature growth, the characteristic peaks of 2H-WS₂ are still well recognizable, but their fwhm is larger than that in the annealed sample, confirming a quite disordered structure. In the as-prepared samples, no features at lower wavenumbers corresponding to 1T-WS₂ have been detected.¹⁰ Because of the clearly discernible Raman features of 2H-WS₂, we suggest the presence of a mixed phase where small seed crystals of 2H-WS₂ coexist with amorphous WS₂. As the sample is annealed, the amorphous areas can rearrange and grow off the already formed 2H seed crystals.

W 4f photoemission spectra can be separated into three single components, two related to WS₂, and the third to WS₃. The W 5p_{3/2} XPS line is found in the same spectral region of the W 4f photoemission line, which results in a broad component in the higher BE tail of the W 4f photoemission line (see brown component in Figure 2); the BEs for each component W 4f_{7/2} lines are reported in Table 1. Comparing the LEED and Raman data (Figure 3) and the XPS literature data, we assigned the lower BE WS₂ component to an amorphous phase and the higher BE one to the 2H-WS₂ phase. The W 4f photoemission line of a WS₂ layer deposited directly

Table 1. Binding Energies (eV) for the Different Components of the W 4f_{7/2} Photoemission Lines for WS₂/Au/Ni(111) and WS₂/h-BN/Au/Ni(111)

	amorphous WS ₂ ⁵³	2H-WS ₂ ¹⁰	WS ₃ ⁵⁴
WS ₂ /Au/Ni(111)	31.6	32.3	33.6
WS ₂ /h-BN/Au/Ni(111)	31.7	32.4	33.6

at 400 °C and separated into chemically shifted components, shows a predominant peak at 32.3 eV, which accounts for 88% of the whole photoemission spectrum. In Figure 4, the

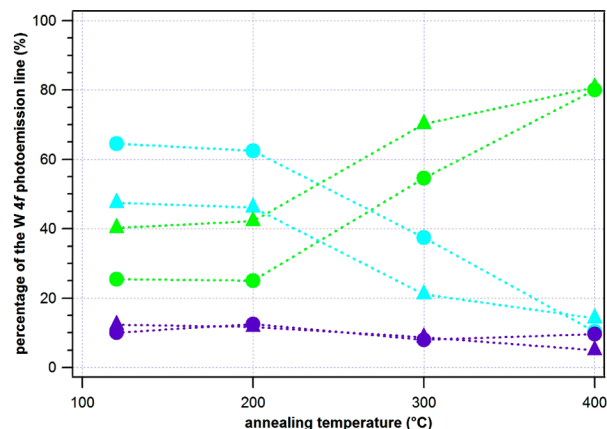


Figure 4. Percentage composition of amorphous WS₂, 2H-WS₂, and WS₃ on the W 4f photoemission lines for WS₂/Au/Ni(111) (circles) and WS₂/h-BN/Au/Ni(111) (triangles). The color code is the same as that in Figure 2.

percentage of composition for each component of the W 4f photoemission line as a function of annealing temperature is reported (dots with the same color code reported in Figure 2).

As mentioned in the introduction, the layer deposited at low temperature exhibits W4f BEs comparable with the values expected for the 1T-WS₂ phase.^{10,39,41} However, due to the lack of order seen by LEED and to the Raman data (see Figure 3), the XPS data are better interpreted as evidence of an amorphous WS₂ layer. It is clear from Figure 4 that thermal treatment transforms the amorphous WS₂ layer into the 2H-WS₂ phase. The presence of a component related to WS₃ in XPS data, which remains constant with annealing temperature (Figure 4), can be explained as nonstoichiometric, sulfur-rich WS_{2+x} species formed at the edges of WS₂ islands. In Raman spectra, amorphous WS₃ species, which are characterized by a spectral fingerprint at 460 and 520 cm⁻¹,⁵¹ were not detected suggesting that WS₃ is not a reaction intermediated of the formation of 2H-WS₂, as it is in the sulfurization of WO₃ to WS₂,⁵¹ or the decomposition of (NH₄)₂WS₄.⁵²

In the VB UPS data of the sample deposited at 120 °C (Figure 5), we can observe a strong attenuation of the substrate

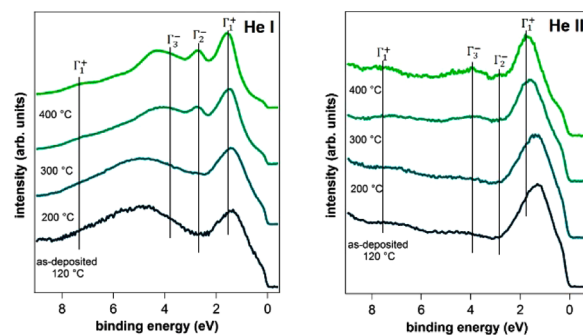


Figure 5. VB photoemission spectra of WS₂/Au/Ni(111) as-deposited at 120 °C and subsequently annealed at higher T in UHV, acquired with He I (21.2 eV, pass energy = 2 eV) and He II (40.8 eV, pass energy = 10 eV). The features were linked to symmetry of S p orbitals based on ref 43.

bands due to the presence of a fully covering WS₂ single layer film and the appearance of new broad features at about 1.3, 4.4, and 6.9 eV. After annealing at 300–400 °C, these peaks become sharper and slightly shift their BE positions to 1.7, 3.9, and 7.4 eV, respectively, while a new state appears at 2.8 eV. All of these features can be labeled according to the symmetry driven combinations between W *5d* and S *3p* orbitals (space group $P\bar{6}m2(D_{3h}^1)$) (see Figure 6). The latter in monolayer 2H-

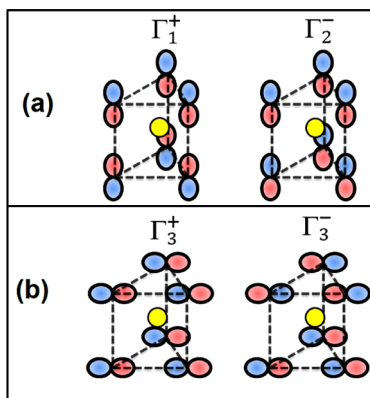


Figure 6. Symmetry combinations of (a) p_z and (b) p_x/p_y sulfur orbitals in a monolayer 2H-WS₂ unit cell with symmetry labels used for the irreducible representations of the space group $P\bar{6}m2(D_{3h}^1)$.

WS₂ can combine into four bands with different symmetries, i.e., Γ_1^+ , Γ_2^- , Γ_3^- . In 2H-WS₂ and more generally in most TMDs, there is a pronounced hybridization between the chalcogenide p and the metal d orbitals.^{55,56} The electronic states that characterize the VB maximum, stem from the hybridization between p_z (Γ_1^+ and Γ_2^-) and d_{z^2} states.⁵⁷ Moreover, the d_{xy} and $d_{x^2-y^2}$ metal orbitals mix with the Γ_3^+ state, whereas the d_{xz} and d_{yz} interact with the Γ_3^- .⁴³ As in a previous work,⁴³ the transition involving Γ_3^- is difficult to discern because of the low photoionization cross section.

Growth of WS₂/h-BN/Au/Ni(111). In order to grow single layer WS₂ on a quasi-freestanding, ultrathin insulator, WS₂ was grown on h-BN decoupled from Ni(111) by few Au layers (WS₂/h-BN/Au/Ni(111)).

WS₂ was grown at 120 °C and then annealed at 200 °C, 300 °C, and 400 °C. The growth of coherent and ordered interfaces in the WS₂/h-BN/Au/Ni(111) system is difficult because the h-BN layer must be of high quality in order to serve as a good epitaxial substrate for the growth of an ordered WS₂ layer, as reported for WS₂/HOPG.⁴³ In the best conditions, as shown in Figure 7a, the experimental LEED pattern of this heterostructure presents six incommensurate, but azimuthally oriented spots with the spacing expected for 2H-WS₂,³³ which is qualitatively similar to the WS₂/Au/Ni(111) system reported in Figure 3a, this LEED pattern demonstrates the presence of van der Waals epitaxy. Unfortunately, the low image quality makes any precise unit cell estimation unreliable, thus preventing the determination of possible strain or layer relaxation. Also in this case, no LEED pattern was observed for WS₂ grown at 120 °C, further confirming the presence of a prevalent amorphous structure.

Comparing the Raman spectra of WS₂/Au/Ni(111) and WS₂/h-BN/Au/Ni(111), Figures 3 and 7, the features for the as-prepared sample indicate a more disordered layer in the case of WS₂/h-BN/Au/Ni(111). After annealing, the peaks have a higher fwhm with respect to those of the WS₂/Au/Ni(111)

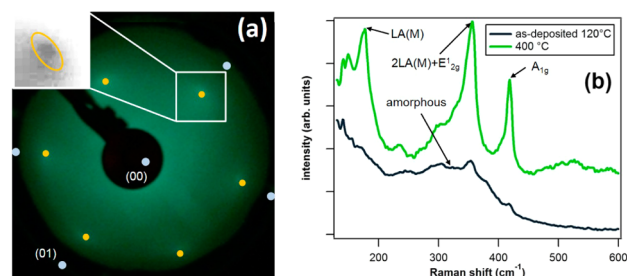


Figure 7. (a) LEED image acquired at 60 eV of WS₂/h-BN/Au/Ni(111) after annealing, the inset reports a magnified view of a WS₂ diffraction spot, white circles indicate calculated positions of Ni(111) diffraction spots. (b) Raman spectra of WS₂/h-BN/Au/Ni(111) acquired with an excitation wavelength of 532 nm, before and after annealing at 400 °C.

system. As in the case of WS₂/Au, because of the presence of 2H features in Raman spectra, it is likely that 2H-WS₂ nanodomains form at low temperature and serve as a seeds during annealing. Therefore, combined evidence from LEED and Raman spectroscopy (Figure 3 vs Figure 7) shows that Au has a higher templating effect than h-BN for the growth of 2H-WS₂. This can be explained by assuming that the interaction between the WS₂ and h-BN is very weak, whereas the interaction with Au is stronger. This is in agreement with previous experiments on the growth of MoS₂ on Au(111) and HOPG, while in the case of Au(111) the interaction with the substrate is stronger and a clear epitaxial relationship is observed, in the case of HOPG disorder is enhanced.^{58,59}

Also in this case, the disappearance of the diffraction spots of the substrate in the LEED pattern and the intensity ratio between the bands at 354 and 417 cm⁻¹ less than one³ indicate the presence of single layer WS₂.

XPS data indicate a similar trend in phase structure for WS₂/h-BN/Au/Ni(111) compared to WS₂/Au/Ni(111) the fraction of the 2H-phase increases with increasing annealing temperature (Figure 4). Interestingly, for the WS₂/h-BN/Au/Ni(111) system, the WS₃ photoemission signals decrease with annealing temperature. Indeed, dosing in our conditions (2×10^{-8} mbar at 400 °C for 15 min.) on Au (~ 6 ML)/Ni(111) results in various stable superstructures.^{49,50} We speculate that WS₃ is abundant at the edges of the WS₂ nanoparticles. Therefore, because of the lower affinity for S to bind to h-BN, the formation of a nonstoichiometric, sulfur-rich WS_{2+x} is unfavorable with respect to Au.

Interestingly, the W 4f photoemission spectra corresponding to amorphous and 2H-WS₂ are shifted 0.1 eV to higher BEs with respect to the WS₂/Au/Ni(111), while maintaining their separation of 0.7 eV, indicating a slightly different electronic coupling, see Table 1. Additionally, the VB UPS data of the monolayer WS₂/h-BN/Au/Ni(111) (Figure 9), show features very similar to those reported for WS₂/Au/Ni(111) (Figure 5). The spectra are mostly dominated by the presence of the outermost layer of WS₂ as expected for a fully covering single layer films; however, they show a barely visible additional state at ~ 4.35 eV related to the σ band of quasi-freestanding h-BN (see Figure 1c).^{44,48} Even when WS₂ is placed on an insulator, there is no large energy shift of its bands with respect to WS₂/Au. This can be explained by the absence of strong interlayer coupling between WS₂ and both Au and h-BN.^{23–25} Similar to WS₂/Au/Ni(111), annealing at high temperature leads to a transition from broad spectral features to sharper ones, which is

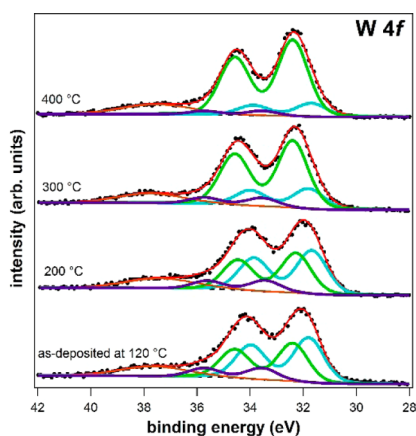


Figure 8. W 4f photoemission spectra of WS₂/h-BN/Au/Ni(111) as-deposited at 120 °C and subsequently annealed at 200 °C, 300 °C, and 400 °C. Measured data, Shirley background and total fit are represented with black dots, dashed black line, and solid red line, respectively. Photoemission lines of amorphous WS₂, 2H-WS₂, WS₃, W 5p_{3/2} are shown with blue, green, purple, and brown solid lines, respectively.

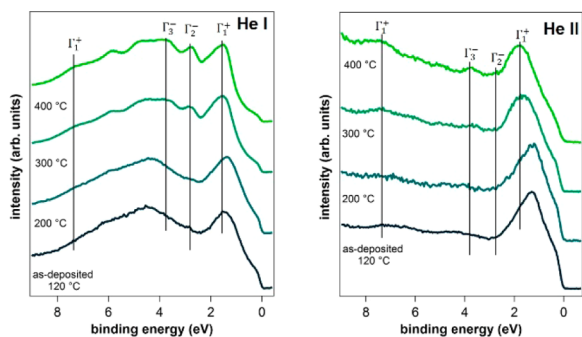


Figure 9. VB spectra of WS₂/h-BN/Au/Ni(111) as-deposited at 120 °C and subsequently annealed at higher T in UHV, acquired with He I (21.2 eV, pass energy = 2 eV) and He II (40.8 eV, pass energy = 10 eV). The features were linked to symmetry of S *p* orbitals based on ref 43.

correlated with Raman spectroscopy (Figure 7), indicating a transition from predominantly amorphous to single layer 2H-WS₂. For the as-deposited layer, Raman spectra show a broad band centered at ~300 cm⁻¹, but there are still small peaks present in the position of 2H-WS₂. For the as-deposited sample of WS₂/Au/Ni(111), there are no clear Raman features of 1T-WS₂ or of WS₃ which suggests a growth mechanism similar to that on the Au/Ni(111) substrate.

Recently, ARPES revealed the opening of a mini-gap in the graphene π orbitals with the out-of-plane states of the TMDC when placed on an MoS₂ single crystal.⁶⁰ We investigated by ARPES with variable-polarization synchrotron radiation an in situ grown WS₂/h-BN heterostructure, in order to identify the band character of our stacked materials and the presence of possible modifications induced by interfacial interactions. The VB spectra of 1 ML of WS₂ deposited on h-BN/Au/Ni(111) along the Γ -M direction with two perpendicular linear polarizations are reported in Figure 10a,b. Since the angle of light incidence on the sample surface is 45°, a linear horizontal polarization vector can be decomposed in two components in and out of the surface plane, while the linear vertical polarization is mainly in the surface plane and along the dispersion direction. We identify three main band structure

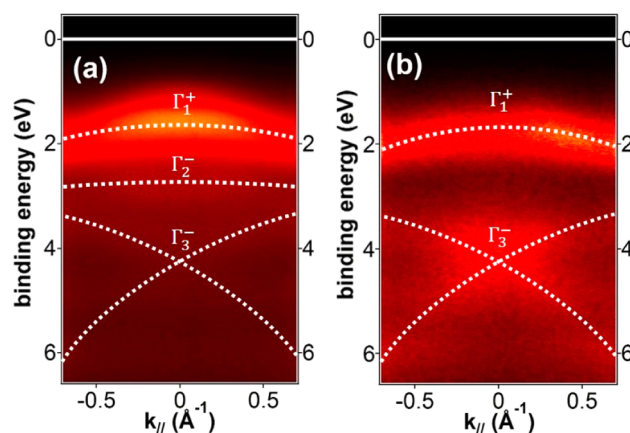


Figure 10. ARPES spectra obtained with synchrotron light at 40 eV with (a) linear horizontal polarization and (b) linear vertical polarization. The features were linked to the symmetry of S 3*p* orbitals based on ref 43.

features at 1.5, 2.8, and 4 eV at the Γ point. Notably, the absence of a band (Γ_4^-) at ~1 eV is a distinctive electronic feature of single layer WS₂.⁴³

The first band at 1.5 eV originates from the hybridization of W 5*d*_{z²} and Γ_1^+ S 3*p*_z orbitals, (see Figure 6) and is particularly emphasized with horizontal polarization (out of surface plane). The second band, at 2.8 eV, can be observed with horizontally polarized radiation and comes from symmetrically different *p*_z orbitals (Γ_2^-). The third feature visible in Figure 10a, derives from the Γ_3^- states mixed with W *d*_{xz} and *d*_{yz} orbitals. These states generate two distinct bands that cross in the Γ point at a BE of 4 eV. The use of linearly polarized radiation in the surface plane suppresses the band at 1.5 eV, whereas the band at 2.8 eV becomes almost undetectable. On the contrary, the bands that are a result of the hybridization of *p*_x and *p*_y orbitals, Γ_3^- , become highly emphasized.⁴³

It is interesting to observe that the energy separation between the bands at the Γ point is the same as that observed for UHV exfoliated WS₂ single crystal or epitaxial WS₂ films grown in situ on HOPG under UHV conditions.⁴³ This indicates the extremely good quality of our films: operating in UHV conditions allows the elimination of any source of contamination and the preparation of films with low defect concentration, which therefore are very prone to any electronic interaction. Monolayer WS₂ supported on h-BN (insulator), HOPG (semimetal), or Au (metal) presents very similar electronic structure. For this reason, an efficient modulation of the electronic properties requires alternative approaches to van der Waals epitaxy.

CONCLUSIONS

We studied the growth of a WS₂ monolayer on gold and on quasi-freestanding h-BN by using XPS, UPS, Raman spectroscopy, and LEED. The latter indicates that although the WS₂ film is incommensurate with respect to the substrate, there is evidence for van der Waals epitaxy. Nevertheless, photoemission VB measurements reveal the absence of interlayer coupling, so that WS₂ supported either on insulating h-BN or metal Au presents the same electronic structure. This outcome is not unexpected considering the high chemical perfection and absence of any possible contaminants in systems grown under UHV conditions. These results suggest that Au is a perfect candidate for the preparation of metal contacts, whereas h-BN

can be used as an ideal substrate to support monolayer WS₂ with the aim of keeping intact its intrinsic properties such as photoluminescence.⁶¹

The WS₂ film deposited at low temperature on both substrates shows a W 4f photoemission line centered at BE very close to the values reported in the literature for 1T-WS₂.^{10,39,41} However, our data indicate that similar spectra can be obtained on amorphous WS₂ that can be converted to crystalline 2H-WS₂ after annealing at 300–400 °C. For the as-deposited samples (at 120 °C), our data suggest the formation of a mixed phase, i.e., primarily an amorphous phase with crystalline 2H-WS₂ seeds. Therefore, our data suggest that amorphous WS₂ could be erroneously identified as 1T-WS₂ on the basis of the simple XPS fingerprint. This must be taken into account when XPS measurements are used as a quantitative technique to estimate the 1T/2H ratio in WS₂-based materials.

Finally, our method for growing heterostructures under UHV conditions can be exploited as a quite general strategy to synthesize and study the pristine properties of other artificially stacked materials. For example, graphene can be grown on Ni(111) and decoupled with gold,⁶² as done here for h-BN; tungsten can be replaced by other transition metals, i.e., Mo or Ni, so that a full gamut of TMDs can be easily obtained. This provides an alternative and more reliable route with respect to ex situ CVD synthesis or mechanical transfer method, for the fundamental study of the authentic properties of complex heterostructures.

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Notes

The authors declare no competing financial interest.

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